
Oral presentation | 8 Plasma Electronics | 8.2 Plasma deposition of thin film, plasma etching and surface treatment

[18a-C309-1~10]8.2 Plasma deposition of thin film, plasma etching and surface treatment

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△ : Presentation by Applicant for JSAP Young Scientists Presentation Award

▲ : English Presentation

▼ : Both of Above

No Mark : None of Above

10:00 AM - 10:30 AM

[18a-C309-5][INVITED] Cyclic etching of tin-doped indium oxide using hydrogen-induced modified layer

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